



ABV-INDIAN INSTITUTE OF INFORMATION TECHNOLOGY & MANAGEMENT GWALIOR

Major Theory Exam (2024-2025)

2023BEE012

Duration: 3:00 Hours  
Max. Marks: 50

BEE-III  
Faculty: Dr. Alok Kumar Kamal

Date: 02/12/2024  
Time: 02:00 PM - 05:00 PM

*Important Instructions:*

- This is a closed book, closed notes examination.
- All sections are compulsory.
- Calculators are allowed.

**Section A**

- 1) Draw the current flow mechanism involved P<sup>+</sup>N diode? [2]
- 2) Explain accumulation, depletion and inversion modes of N-MOSCAP with the help of appropriate diagram and conditions. [2]
- 3) Define short channel effects and discuss Drain Induced Barrier Lowering (DIBL). [2]
- 4) What is the type of parasitic charges that exist within the oxide as well as at oxide/silicon interface. [2]
- 5) Why C-V characteristics for ideal MOSCAP behave differently for low and high frequency. Give detailed explanation. [2]
- 6) Consider the MOS structure for an oxide thickness of  $t_{ox} = 200 \text{ \AA}$  and an equivalent density of oxide charge ( $Q'_{ox} = 8 \times 10^{10} / \text{cm}^2$ ), calculate the flat-band voltage. [2]  $\phi_{ms} = -1.13$
- 7) Why we cannot use square law equation of drain current beyond  $V_{DS} = V_{DSsat}$ . [2]
- 8) How is gradual channel approximation different from Depletion approximation. [2]
- 9) What is channel length modulation and how it is modelled in the drain current equation of MOSFET. [2]
- 10) What is pinch-off in MOSFET. [2]

**Section B**

- 1) Explain why threshold voltage changes when source to bulk junction is reversed biased. Also, derive the expression for change in threshold voltage with impact of body effect. [5]
- 2) Define threshold voltage of a practical MOSFET and derive the expression. [5]



*Microelectronic device and Materials (EE203)*

- 3) Consider a p-type silicon substrate at  $T = 300^\circ\text{K}$  doped with  $N_A = 3 \times 10^{16} / \text{cm}^3$ . Assume density of oxide charge  $Q'_{ox} = 10^{11} / \text{cm}^2$ . Determine the threshold voltage such that the oxide thickness is  $t_{ox} = 504^\circ\text{\AA}$ . The work function difference is  $\phi_{ms} = -1.13 \text{ V}$  [5]
- 3) Discuss N<sup>+</sup>P junction under thermal equilibrium, and illustrate concentration, space charge, electric field and potential profile plot, with proper explanation. [5]
- 4) Derive the drain current equation for normally off NMOS transistor with clear schematic and explanation. [10]